

SEMICONDUCTOR STRUCTURE AND METHOD FOR MANUFACTURING SAME

ABSTRACT

Embodiments of the disclosure relate to the field of semiconductors, and provide a semiconductor structure and a method for manufacturing the same. The semiconductor structure includes: a base (11); a bit line (104); and a semiconductor channel (105) including a first doped region (I), a channel region (II), and a second doped region (III) that are sequentially arranged, where the first doped region (I) contacts the bit line (104), and the first doped region (I), the channel region (II), and the second doped region (III) are doped with first-type doped ions. The channel region (II) is further doped with second-type doped ions, enabling a concentration of majority carriers in the channel region (II) to be less than a concentration of majority carriers in the first doped region (I) and a concentration of majority carriers in the second doped region (III). The first-type doped ions are one of N-type ions or P-type ions, and the second-type doped ions are the other of N-type ions or P-type ions. The embodiments of the disclosure help to improve the electrical performance of a semiconductor structure.

[Fig. 1]